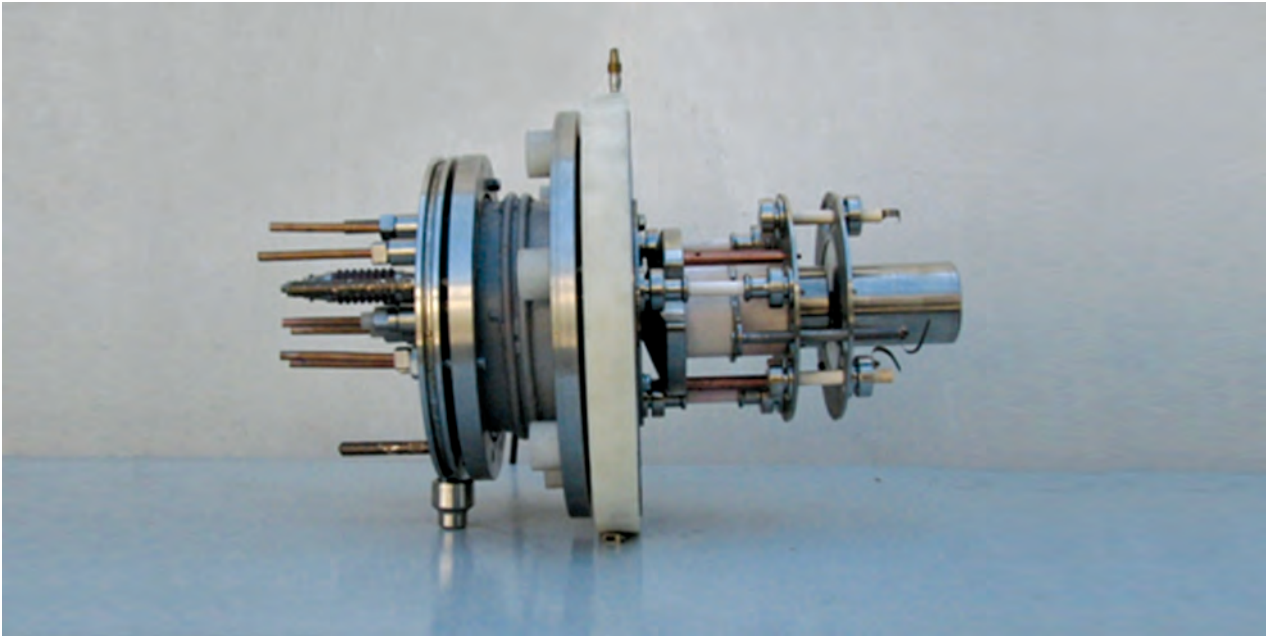


HIGH-PERFORMANCE SOURCE OF MULTIPLY CHARGED METAL IONS



Areas of Application

The device is to be used for ion implantation of materials with single/double-charged metal ions (Be, Fe, Cr, Ni, Zr, Mo, W, etc.) and simulation studies of ion irradiation effects on construction materials of nuclear and thermonuclear industry

Specification

Ions	Be, Fe, Cr, Ni, Zr, Mo, W
Ion current, μA	10–200
Ion energy, keV	30
Ion charge	+1, +2
Power consumption, W	1000

IPR Protection

IPR1, IPR2

Advantages

The metal ion source enables to generate beams of single- and double-charged metal ions based on ion-plasma sputtering. The technique applied for creation of operating environment enables forming an atomic concentration and a high-density plasma of almost all metals (Be, Fe, Cr, Ni, Zr, Mo, W and others) without high-temperature heating of the source

Stage of Development.

Suggestions for Commercialization

IRL3, TRL4

Manufacture of single samples by ourselves or jointly with potential partners

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